

Custome Attorney Docket No. 0432

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit: 2823

Examiner: Lee, Hsien Ming CRATER In re Application of: Gaku MINAMIHABA, et al. Serial No.: 09/932,943 Filed: August 21, 2001 SLURRY FOR CHEMICAL For: MECHANICAL POLISHING AND METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE **Assistant Commissioner for Patents** Washington, DC 20231

Sir:

RESPONSE TO RESTRICTION REQUIREMENT

In the Restriction Requirement dated September 11, 2002, with a period for response extending through October 11, 2002, the Examiner required restriction under 35 U.S.C. § 121 between Group I (claims 1-17) and Group II (claims 18-25). Applicants provisionally elect to prosecute Group II, claims 18 - 25, as thus characterized by the Examiner.

Please grant any extensions of time required to enter this response and charge any additional required fees to our deposit account 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER, L/L.P.

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Dated: October 3, 2002

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